

# Working Group 4 - Applications

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- Microprobing of biological cells and tissue for cancer studies and treatments
- X-ray micro- and nano-imaging for, eg, bio-medical issues, also exploiting phase contrast techniques
- X-ray mammography exploiting monochromatic sources and phase contrast methodologies
- In-the-field measurements of pollutants, eg, particulates
- In-the-field measurements of structural and compositional characteristics of materials related to cultural heritage
- EUV lithography and metrology
- XUV photoabsorption studies of atoms and ions
- Metrology of nanostructures
- Investigation of isochoric heating and  $K_{\alpha}$  generation in laser plasmas
- Time-Resolved X-ray Diffraction by Using Table-Top Laser Plasma Sources
- Innovative XUV and X-ray Plasma Spectroscopy to Explore Extreme States of Matter

# Multidisciplinary Applications

- 1. Investigations of elemental content, microporosity, etc. of rocks using ion and X-ray microprobes**
- 2. Investigation of Porcelain Art by Means of Combined  $\mu$ PIXE and  $\mu$ CT Measurements**
- 3. Case studies on utilization of synchrotron radiation and lab based sources for  $\mu$ CT of biominerals**
- 4. X-ray microbeam facility for single cell irradiation; results of first experiments on cancer cells**
- 5. Improved biocompatibility of surfaces by EUV treatment**
- 6. Graphene Oxide reduction by an EUV laser source**

# X-Ray microscopy

1. EUV dark-field microscopy for defect inspection
1. X-ray wave guide for phase contrast microscopy with laboratory source
2. High-Definition X-Ray Polarimetry
3. X-ray microscope development for water window imaging

# Surface Modification and Nanopatterning

- 1. Interaction of EUV pulses with solids: investigation of surface structure and ablation products**
- 2. Physico-chemical surface modification of polymers using a laser-plasma EUV source**
- 3. Application of laser plasma EUV sources in processing polymers and nanoimaging**
- 4. Damage and ablation of optical materials under focused EUV radiation from a table-top LPP source**
- 5. Time resolved EUV pump-probe microscopy of fs-laser induced nanostructure formation**

# Lithography and Metrology

- 1. 13.5 nm lithography systems using Xe and Sn sources**
- 2. Beyond EUV lithography at 6x nm, development of sources**
- 3. Resolution enhancement in short wavelength and X-ray lithography**
- 4. Development of systems for mass blank inspection at 13.5 nm**
- 5. Laboratory based extreme ultraviolet reflectometry for analysis of ultra thin films**
- 6. Novel anti-counterfeiting technique by EUV lithography using EUV irradiation of LiF**

# Coherent EUV/ X-ray production – Photoionization Processes

1. Applications of free electron laser (FEL) radiation
1. Applications of discharge x-ray laser systems
1. Multiphoton ionization in intense EUV free electron laser fields
1. High harmonic production and applications (CDI)
1. X-ray and IR cross correlation experiments at the LCLS free electron laser facility

# What next ?

## (Challenges & Opportunities)

**Strong focus on EUV and X-ray metrology –**  
LPP, DPP, XRTs, Synchrotrons, Free Electron Lasers,...

**Future pre-doctoral and doctoral training**

**Further ‘real world and problem-driven’  
academic-industrial collaboration**

**EUVL – key bottleneck remains - source flux  
limitation.....**